

## INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

ATTY. DOCKET NO.  
CLV-31563P1  
APPLICATION NO.  
09/911,218  
APPLICANT  
QIU ET AL.  
FILING DATE  
JULY 23, 2001

Group



## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
<i>Jem</i>	AA	US 6, 020,175	2/1/00	Onda et al	435/	180	9/10/97
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						

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NOV 21 2003  
TC 1700

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	OFFICE	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AM						<input type="checkbox"/>	<input type="checkbox"/>
	AN						<input type="checkbox"/>	<input type="checkbox"/>
	AO						<input type="checkbox"/>	<input type="checkbox"/>
	AP						<input type="checkbox"/>	<input type="checkbox"/>
	AQ						<input type="checkbox"/>	<input type="checkbox"/>

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent pages, Etc.)

<i>Jem</i>	AR	Patterned Polymer Multilayer Fabrication By Controlled Adhesion Of Polyelectrolytes To Plasma-Modified Fluoropolymer Surfaces By Vargo, Calvert, Wynne, Avlyanov, MacDiarmid, & Rubner 1966.
<i>Jem</i>	AS	Molecular Self Assembly of Conducting Polymers: A New Layer-By-Layer Thin Film Deposition Process. By Cheung, Fou, Ferreira, & Rubner. MIT
	AT	

EXAMINER

*Jennifer Kolb Michener*

DATE CONSIDERED

*5/14/04*

\*EXAMINER: Initial of reference considered, whether or not citation is in conformance with MPEP 609: Draw a line through citation if not in conformance and not considered. Include a copy of this form with the next communication to applicant.